### Dielectric Properties and Crystal Structure of Aluminum Oxide (Al<sub>2</sub>O<sub>3</sub>) at Different Molar

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**Abstract:** In this work preparing  $Al_2O_3$  samples were prepared by the sol-gel method with different molar (0.1, 0.2 and 0.3M). The optical properties of the  $(Al_2O_3)$  samples were investigated. In particular, optical parameters such as the optical band gap, absorption coefficient, refractive index and extinction coefficient, real and imaginary dielectric constant were comprehensively studied. A number of samples were prepared by Sol-gel method. It is found that the optical absorbance wavelength range was (370–390) nm. Also the morphology characteristics of crystal structure of samples have been investigated by XRD and using optical method to investigate the electrical properties; and the results were as follow: the existence of the (022) at 34.87<sup>o</sup>, (111) at 38.35<sup>o</sup>, (202) at 45.23<sup>o</sup>, (020) at 54.53<sup>o</sup>, (113) at 58.59<sup>o</sup> and (311) at 61.48<sup>o</sup>

Major lattice planes in the XRD patterns confirms the formation of spinal Monoclinic, Miller indices provided in the figure and all peaks determine transformation of dried .The results indicate the sample have good characteristics for optoelectronic applications.

**Keywords:** Aluminum Oxide, Sol-gel method, reail and imajanery dielectric constant, optical and electrical conductivity

#### Introduction

Transparent conducting oxides (TCOs) are electrical conductive materials with a comparably low absorption of light. (TCO) samples have emerged as excellent candidates due to interest in their promising applications in next-generation electrode. A wide variety of transparent conductors in terms of new materials are becoming available that could serve as an alternative to ITO [1]. ITO is one of the best transparent conductors, but indium is quite expensive [2]. The electrodes fabricated utilizing TCO samples in optoelectronic devices have excellent physical properties of high visible transmittance, low resistivity, high infrared reflectance, and large absorbance [3]. Because Al<sub>2</sub>O<sub>3</sub>materials are large-band-gap semiconductors with peculiar physical properties of high chemical stabilities and large excitons binding energies, they are of current interest due to their potential applications in optoelectronic devices, such as photo detectors, solar cells, light-emitting diodes, and laser diodes. Low-resistivity Al<sub>2</sub>O<sub>3</sub>samples may be realized by using several dopants, such as, Ga, and in of the group III [4]. Aluminum doped zinc oxide (AZO) coatings exhibit high transparency and low resistivity and these materials are suitable for fabricating transparent electrodes in solar cells, gas sensors and ultrasonic oscillators. They are also found in applications such as surface acoustic devices, optical waveguides and micromachined actuators. They are an alternative material to tin oxide and indium tin oxide, which has been most, used up to date [4]. For the most used (ITO) as a transparent conducting oxide which has transmittance ( $\geq 90\%$ ), low specific resistance ( $\leq 10-3 \Omega$ /cm) in the visible rays area, so it is used as the transparent electrode of the solar cell, display fields widely. But the raw materials of ITO are expensive, and it has weak point of the degradation phenomenon and toxicity when it is exposed in the hydrogen plasma [4-2]. Ohyama reported that the use of 2-methoxyethanol and mono ethanolamine, solvents with high boiling point, resulted in transparent  $Al_2O_3$  samples with strongly preferred orientation and that better electrical and optical properties had been obtained in 0.5 at. % aluminum doped ZnO thin films heated in reducing atmosphere. Nunes found that when the doping concentrations of Al, in and Ga were 1, 1 and 2 at %, respectively, electrical and optical properties of doped ZnO were superior [2]. Various techniques such as molecular beam epitaxial (MBE) [6], pulse laser deposition (PLD) [7], magnetron sputtering [8], chemical vapor deposition (CVD) [9], atomic layer deposition [10], electron beam evaporation [11], hydrothermal method, and sol-gel process have been applied to ZnO thin film preparation[11]. The sol-gel method has distinct potential advantages over these other techniques owing to

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its lower crystallization temperature, low cost, simple deposition procedure, easier compositional control, ability to tune the microstructure via sol-gel chemistry, and large surface area coating capability.

#### Material & Method

The precursors used in the synthesis  $Al_2O_3$  by sol-gel process Aluminum nitrate dehydrate Al  $(NO_3)_3.9H_2O$ . The need for surfactant is fulfilled by the use of 2-methoxyethanol (ME)  $CH_3OCH_2CH_2OH$ . The stock solution for the samples was prepared using Aluminum nitrate (0.1M, 0.2 M and 0.3 M) dissolved in 300 ml of ethanol in the glass beaker. Then the solution was stirred for 60 min at 80°C until we get milky solution. Drops from 2-methoxyethanol (ME) was added to the solution as stabilizer to get a transparent solution. We get then the Aluminum-oxide solution. And then kept the Aluminum oxide solution at lab's temperature about 24 hours, then we filter it, and we obtained the Sol ready to be used the samples. After prepared the samples, they were ready for characterization. The molar of the  $(Al_2O_3)$  sample were about (0.1 M, 0.2 m and 0.3 M) for all samples. The optical transmittance and reflectance of the  $(Al_2O_3)$  samples were measured as a function of wavelength by UV-visible spectroscopy, and other optical constant was calculated. The crystal structure of all samples characterized at room temperature using a Philips PW1700 X-ray diffract meter (operated at 40 kV and current of 30 mA) and samples were scanned between 200 and 900 at a scanning speed of 0.06 °C/s using Cu K $\alpha$  radiation with  $\lambda = 1.5418$ Å.



Fig(1): The XRD charts of the (Al<sub>2</sub>O<sub>3</sub>) sample

(size, Miller indices and $d$ – spacing) of the (Al <sub>2</sub> O <sub>3</sub> ) sample						
2-Theta	$X_{s}(nm)$	d( nm )	h	k	L	
34.87	32.4	0.257	0	2	2	
38.35	42.8	0.235	1	1	1	
45.23	33.7	0.200	2	0	2	
54.53	31.9	0.168	0	2	0	
58.59	33.2	0.157	1	1	3	
61.48	38.9	0.151	3	1	1	

	Table (1) some crystallite lattice parameter	
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Fig (3):The relation between reail dielectric constant and wavelengths of three (Al<sub>2</sub>O<sub>3</sub>)samples in different molar ( 0.1M, 0.2~M and 0.3M )



Fig (4):The relation between imagnery dielectric constant and wavelengths of three  $(Al_2O_3)$ samples in different molar ( 0.1M, 0.2 M and 0.3M )



Fig (5):The relation between optical conductivity and wavelengths of three  $\,(\rm Al_2O_3) samples in different molar ( <math display="inline">0.1 M, 0.2~M$  and 0.3 M )



Fig (6):The relation between electrical conductivity and wavelengths of three  $(Al_2O_3)$ samples in different molar (0.1M, 0.2 M and 0.3 M)

#### **Conclusion & Discussion**

The X-ray diffraction patterns of the synthesized of  $(Al_2O_3)$  nano-crystals have been shown in Fig (1). The existence of the (022), (111), (202), (020), (113) and (311) major lattice planes in the XRD patterns confirms the formation of spinal Monoclinic, Miller indices provided in the figure and all peaks determine transformation of dried ( $(Al_2O_3)$  crystallites with Monoclinic retile crystal structure. Table (1), shows the XRD parameters of  $(Al_2O_3)$  nanocrystals at various crystalline orientations. In fig. (2) Shows the relation between absorbance and wavelengths for three samples of  $(Al_2O_3)$ , the rapid increase of the absorption at wavelengths ranged (370 -390 nm). The effects of Aluminum Oxide  $(Al_2O_3)$ molar in the absorbance value increased when the molar increase, also in fig (2) show that the maximal value at 375 nm wavelength. Real Dielectric Constant ( $\varepsilon_1$ )shows in fig(3) the variation of the ealdielectric constant ( $\varepsilon_1$ ) with wavelengthof three samples in different molar (0.1M,0.2 M and 0.3M) that prepared by Aluminum Oxide  $(Al_2O_3)$  which calculated from the relation:

$$\epsilon_1 = n^2 - k^2$$

Where the real the dielectric ( $\epsilon_1$ ) is thenormal dielectric constant .From fig (3)the variation of ( $\epsilon_1$ ) is follow therefractive index, where increased in theregion that  $\lambda > 371$  nmforall Aluminum Oxide (Al<sub>2</sub>O<sub>3</sub>) and 376

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nm , where the absorption of the samples for these wavelength is small, but the polarization was increase. The maximum value of ( $\epsilon_1$ ) equal to (4.66) for all samples at diefferant wavelength near. The effect of treetetment by (Al<sub>2</sub>O<sub>3</sub>) molar increased when ( $\epsilon_1$ ) decreased at wavelength 375.5 nm . But the imaginary dielectric constant ( $\epsilon_2$ )vs( $\lambda$ ) was shown in fig(4) this value calculated from the relation:

 $\epsilon_2 = 2Nk$ 

( $\epsilon_2$ ) represent the absorption associated with free carriers. As shown in fig(4) the shape of ( $\epsilon_2$ ) is thesame as ( $\epsilon_1$ ), this means that therefractive index was dominated in the sebehavior . The maximum values of ( $\epsilon_2$ ) are different according to the tratment operation , so The maximum value of ( $\epsilon_1$ ) equal to (4.66) for all samples at diefferant wavelengthn, while the maximum value of ( $\epsilon_2$ ) equal to (2.19x10<sup>-6</sup>) for all samples at diefferant wavelengthn, these behavior may by related to the different absorption mechanism for free carriers.

Electrical and Optical Conductivity :The optical conductivity is a measure of frequency response of material when irradiated with light which is determined using the following relation:

 $\delta_{opt}\,=\,\frac{\alpha nc}{4\pi}$ 

Where(c) is the light velocity. The electrical conductivity can be estimated using the following relation:  $\delta_{ele} = \frac{2\lambda\delta_{opt}}{\alpha}$ 

The high magnitude of optical conductivity  $(8.73 \times 10^8 \text{ sec}^{-1})$  confirms the presence of very high photoresponse of three  $(Al_2O_3)$ samplesin different molar (0.1M, 0.2 M and 0.3M). The increased of optical conductivity at high photonenergies is due to the high absorbance of elevant samples prepared by  $(Al_2O_3)$ different molar (0.1M, 0.2 M and 0.3M) formand may be due to electron excitation by photon energy as it is shown in Figs (5) and (6).

So it is obvious that these treatments for thin film give a best optical property to be used for optoelectronic applications.

#### References

- [1]. The Effect of Changing Concentrations of Al<sub>2</sub>O<sub>3</sub> On The (ZnO)<sub>X</sub>(Al<sub>2</sub>O<sub>3</sub>)<sub>1-X</sub> Thin Films Absorption And Energy Gap/ 1Zohal E. M. Ebnouf, 2Mahmoud.H.M .Hilo, 3Mubarak Dirar Abdallah, 4Ahmed H.Alfaki, 5Abdalsakhi S M.H & 6Sawsan Ahmed Elhouri Ahmed / International Journal of Scientific Engineering and Applied Science (IJS EAS) – Volume-3, Issue-3, March 2019 ISSN: 2395-3470 www.ijseas.com.
- [2]. Aldesogi Omer Hamed, Nadir A. Mustafa ,Abdalsakhi.S.Mohammd , Montasir Salman ElfadelTyfor . Effect of difference concentrations of Al on the optical properties of AZO thin films -IOSR Journal of Applied Physics (IOSR-JAP) e-ISSN: 2278-4861.Volume 8, Issue 6 Ver. I (Nov. - Dec. 2016), PP 40-45 www.iosrjournals.org DOI.
- [3]. AndreasStadler, Materials 2012, 5, 661-683; doi:10.3390/ma5040661.
- [4]. D.H. Oh, Y.S. No, S.Y. Kim, W.J. Cho, J.Y. Kim and T.W. Kim, Journal of Ceramic Processing Research. Vol. 12, No. 4, pp. 488~491 (2011), 488.
- [5]. Chang, J.F.; Hon, M.H. The effect of deposition temperature on the properties of Al-doped zinc oxide thin films. Thin Solid Films 2001, 386, 79–86.
- [6]. Yim, K. G.; Cho, M. Y.; Jeon, S. M.; Kim, M. S.; Leem, J.-Y. J.Korean Phys. Soc. 2011, 58, 520.
- [7]. Carcia, P. F.; Mclean, R. S.; Reilly, M. H.; Nunes, G. Appl. Phys.Lett. 2003, 82, 1117.
- [8]. Kim, Y.-S.; An, C. J.; Kim, S. K.; Song, J.; Hwang, C. S. Bull.Korean Chem. Soc. 2010, 31, 2503.
- [9]. Kim, M. S.; Yim, K. G.; Jeon, S. M.; Lee, D.-Y.; Kim, J. S.; Kim, J. S.; Son, J.-S.; Leem, J.-Y. Jpn. J. Appl. Phys. 2011, 50, 035003.
- [10]. Kim, M. S.; Yim, K. G.; Leem, J.-Y.; Kim, S.; Nam, G.; Kim, D. Y.; Kim, S.-O.; Lee, D.-Y.; Kim, J. S.; Kim, J. S. J. Korean Phys. Soc. 2011, 59, 346.
- [11]. The Effect Of Changing Al2O3Concentrations And Nano Crystal SizeOn (ZnO) X (Al2O3) 1-X Thin FilmsConductivity And Imaginary ElectricPermittivity /Zohal E. M. Ebnouf, Mubarak Dirar Abdallah, M.H.M.Hilo, Ahmed H.Alfaki, Abdalsakhi S M.H&Sawsan Ahmed Elhouri AhmedIJISET -International Journal of Innovative Science, Engineering & Technology, Vol. 6 Issue 2, February 2019ISSN (Online) 2348 – 7968 www.ijiset.com